



**RIKI GLOBAL**  
performance through innovation

www.rikiglobal.com

**ROMMA**  
PURE CHEMISTRY

Plot No 39 1st Floor Lavanya Aracade Jayabheri Enclave  
Gachibowli Hyderabad-500032.Telangana  
Mob : +91 99082 46685 Tel : 040 - 35172288/89

✉ [info@rikiglobal.com](mailto:info@rikiglobal.com)  [www.rikiglobal.com](http://www.rikiglobal.com)  +91-9908246695 +91-40-35172288/89



**RIKI GLOBAL**  
performance through innovation

## ROMIL-UpS™ Ultra Purity Solvents Specifications

for critical analytical applications

### Acetone UpS

ultra gc

H033

2½LT H033L  
Dgr H:225-319-336-EUH066  
P:210-233-305+351+338



#### (Propanone)

(CH<sub>3</sub>)<sub>2</sub>CO MW 58.08 BP 56.1°C d 0.79 CAS [67-64-1]  
Assay >99.95% Water <0.2% Residue <0.0001%  
Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test  
Application:GC critical lowresidue applications

### Acetonitrile UpS

ultra gc

H054

2½LT H054L  
Dgr H:225-302+312+332-319  
P:210-240-302+352-305+351+338-  
403+233



#### (Methyl Cyanide)

CH<sub>3</sub>CN MW 41.05 BP 81.6°C d 0.78 CAS [75-05-8]  
Assay >99.9% Water <0.02% Residue <0.0001%  
Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test  
Application:GCcritical lowresidue applications

### Acetonitrile UpS

ultra lc

H050

1LT H050M  
2½LT H050L  
Dgr H:225-302+312+332-319  
P:210-240-302+352-305+351+338-  
403+233



#### (Methyl Cyanide)

CH<sub>3</sub>CN MW 41.05 BP 81.6°C d 0.78 CAS [75-05-8]  
Assay >99.9% Water <0.005% Residue <0.0001%  
UV: 190nm >18%; 193nm >50%; 197nm >80%; 215nm >95%; 230-400nm >99%  
Acidity <0.0005 meq/g  
Alkalinity <0.00006 meq/g  
Gradient Use Test: 205nm <0.002 AU; 254nm <0.0005 AU  
Baseline drift <0.02 AU @ 205nm  
Fluorescence (as quinine): 254nm <1 ppb; 365nm <1 ppb  
Suitability for LC-MS passes test  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Application: HPLC criticalgradient applications, LC-MS, UHPLC

### Acetonitrile UpS

ultra pfas

H052

2½LT H052L  
Dgr H:225-302+312+332-319  
P:210-240-302+352-305+351+338-  
403+ 233



#### (Methyl Cyanide)

CH<sub>3</sub>CN MW 41.05 BP 81.6°C d 0.78 CAS [75-05-8]  
Assay >99.9% Water <0.005% Residue <0.0001%  
UV: 190 nm >18%; 193nm >50%; 197 nm > 80%; 215nm >95%; 230-400nm >99%  
Acidity <0.0005 meq/g  
Alkalinity <0.00006 meq/g  
Gradient Use Test: 205nm <0.002 AU; 254nm <0.0005 AU  
Baseline drift <0.02 AU @ 205nm  
Fluorescence (as quinine): 254nm <1 ppb; 365nm <1 ppb  
Suitability for LC-MS passes test  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Suitability for PFAS analysis passes test  
Application: Ultra low background solvent for LC-MS analysis of poly- and per-  
uoroalkyl substances

### Dichloromethane UpS

stabilised with amylene ultra lc

H204

2½LT H204L  
Wng H:351  
P:281-308+313



#### (Methylene Dichloride)

CH<sub>2</sub>Cl<sub>2</sub>MW 84.93 BP 39.6°C d 1.33 CAS [75-09-2]  
Assay >99.9%\* Water <0.01% Residue <0.0001%  
UV: 235nm >10%; 240nm >50%; 245nm >80%; 250nm >95%; 265-400nm >99%  
\*ex stabiliser  
Stabiliser: Amylene ca. 25 ppm  
Gradient Use Test: 260nm <0.0005 AU  
Application: HPLC critical gradient applications, UHPLC

### Dichloromethane UpS

stabilised with cyclohexene/amylene ultra gc

H205

2½LT H205L  
Wng H:351  
P:281-308+313



#### (Methylene Dichloride)

CH<sub>2</sub>Cl<sub>2</sub>MW84.93BP 39.6°C d 1.33 CAS [75-09-2]  
Assay >99.9%\* Water <0.01% Residue <0.0001% \*ex  
stabiliser Stabiliser: Cyclohexene/Amylene ca. 50/25  
ppm Suitability for GC-FID: passes test Suitability for  
GC-ECD: passes test Suitability for GC-MS: passes  
test Application: GC critical low residue applications





**RIKI GLOBAL**  
performance through innovation

## ROMIL-UpS™ Ultra Purity Solvents Specifications

for critical analytical applications

Ethyl Alcohol (see Ethanol)

### Ethanol absolute UpS

ultra lc

H317

2½LT H317L  
Dgr H:225  
P:210-233-240-403+235



(Ethyl Alcohol)

C<sub>2</sub>H<sub>5</sub>OH MW 46.07 BP 78.3°C d 0.79 CAS [64-17-5]

Assay >99.8% Water <0.1% Residue <0.0001%

UV: 205nm >10%; 220nm >50%; 240nm >80%; 250nm >95%; 270-400nm >99%

Gradient Use Test: <0.005 AU @ 260nm

Fluorescence (as quinine): 254nm <2 ppb

Application: HPLC critical gradient applications, UHPLC

### Ethyl Acetate UpS

ultra lc

H347

2½LT H347L  
Dgr H:225-319-336-EUH066  
P:210-233-240-305+351+338-403+235



CH<sub>3</sub>COOC<sub>2</sub>H<sub>5</sub> MW 88.11 BP 77.1°C d 0.90 CAS [141-78-6] Assay >99.9%

Water <0.005% Residue <0.0001% UV: 255nm >10%; 260nm >50%; 265nm

>80%; 270nm >95%; 310-400nm >99% Gradient Use Test: <0.0005 AU @

290nm Application: HPLC critical gradient applications, UHPLC

### n-Heptane 99% UpS

ultra gc

H364

2½LT H364L  
Dgr H:225-304-315-336-410  
P:210-273-301+310-331-302+352-304+340-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>5</sub>CH<sub>3</sub> MW 100.21 BP 98.4°C d 0.68 CAS [142-82-5] Assay

>99% Water <0.01% Residue <0.0001% Suitability for GC-FID passes test

Suitability for GC-ECD passes test Suitability for GC-MS passes test

Application: GC critical low residue applications

### n-Heptane 99% UpS

ultra lc

H363

1LT H363M  
2½LT H363L  
Dgr H:225-304-315-336-410  
P:210-273-301+310-331-302+352-304+340-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>5</sub>CH<sub>3</sub> MW 100.21 BP 98.4°C d 0.68 CAS [142-82-5] Assay >99%

Water <0.005% Residue <0.0001% UV: 195nm >10%; 210nm >50%; 220nm

>80%; 245nm >95%; 290-400nm >99% Acidity <0.0002 meq/g Alkalinity

<0.0002 meq/g Trace ionic impurities: Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10

ppb each Al, Ca <25 ppb each Na <50 ppb Application:

HPLC critical applications, LC-MS, UHPLC

### n-Hexane 95% UpS

ultra lc

H391

2½LT H391L  
Dgr H:225-304-361f-373-315-336-411  
P:210-240-273-301+310-331-302+352-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>4</sub>CH<sub>3</sub> MW 86.18 BP 67-70°C d 0.66 CAS [110-54-3] Water

<0.005% Residue <0.0001% UV: 190nm >10%; 205nm >50%; 220nm >80%;

235nm >95%; 255-400nm >99% Assay (n-isomer) >95% Assay (all isomers)

>99.5% Gradient Use Test: <0.0005 AU @ 260nm Application: HPLC

critical gradient applications, UHPLC

### n-Hexane 99% UpS

ultra gc

H394

2½LT H394L  
Dgr H:225-304-361f-373-315-336-411  
P:210-240-273-301+310-331-302+352-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>4</sub>CH<sub>3</sub> MW 86.18 BP 68.7°C d 0.66 CAS [110-54-3] Assay >99%

Water <0.01% Residue <0.0001% Suitability for GC-FID passes test

Suitability for GC-ECD passes test Suitability for GC-MS passes test

Application: GC critical low residue applications





**RIKI GLOBAL**  
performance through innovation

## ROMIL-Ups™ Ultra Purity Solvents Specifications


for critical analytical applications

### n-Hexane 99% Ups

#### ultra lc

H395

1LT H395M  
2½LT H395L  
Dgr H:225-304-361F-373-315-336-411  
P:210-240-273-301+310-331-302+352-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>4</sub>CH<sub>3</sub> MW 86.18 BP 68.7°C d 0.66 CAS [110-54-3]  
Assay >99% Water <0.005% Residue <0.0001%  
UV: 190nm >10%; 205nm >50%; 220nm >80%; 235nm >95%; 255-400nm >99%  
Acidity <0.0002 meq/g  
Alkalinity <0.0002 meq/g  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Application: HPLC critical applications, LC-MS, UHPLC

**Methyl Alcohol (see Methanol)**

**Methyl Cyanide (see Acetonitrile)**


**Methylene Dichloride (see Dichloromethane)**

### Methanol Ups

#### ultra gc

H415

2½LT H415L  
Dgr H:225-301+311+331-370  
P:210-280F-302+352-309+310-403+235




(Methyl Alcohol)  
CH<sub>3</sub>OH MW 32.04 BP 64.5°C d 0.79 CAS [67-56-1]  
Assay >99.9% Water <0.02% Residue <0.0001%  
Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test  
Application: GC critical low residue applications

### Methanol Ups

#### ultra lc

H411

1LT H411M  
2½LT H411L  
Dgr H:225-301+311+331-370  
P:210-280F-302+352-309+310-403+235




(Methyl Alcohol)  
CH<sub>3</sub>OH MW 32.04 BP 64.5°C d 0.79 CAS [67-56-1]  
Assay >99.9% Water <0.02% Residue <0.0001%  
UV: 205nm >10%; 210nm >50%; 225nm >80%; 240nm >95%; 265-400nm >99%  
Acidity <0.0003 meq/g  
Alkalinity <0.0002 meq/g  
Gradient Use Test: 230nm <0.002 AU; 254nm <0.002 AU  
Baseline drift <0.02 @ 230nm  
Fluorescence (as quinine): 254nm <1 ppb; 365nm <1 ppb  
Suitability for LC-MS passes test  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Application: HPLC critical gradient applications, LC-MS, UHPLC

### Methanol Ups

#### ultra pfas

H414

2½LT H414L  
Dgr H:225-301+311+331-370  
P:210-280F-302+352-309+310-403+235



(Methyl Alcohol)  
CH<sub>3</sub>OH MW 32.04 BP 64.5°C d 0.79 CAS [67-56-1]  
Assay >99.9% Water <0.02% Residue <0.0001%  
UV: 205nm >10%; 210nm >50%; 225nm >80%; 240nm >95%; 265-400nm >99%  
Acidity <0.0003 meq/g  
Alkalinity <0.0002 meq/g  
Gradient Use Test: 230nm <0.002 AU; 254nm <0.002 AU  
Baseline drift <0.02 @ 230 nm  
Fluorescence (as quinine): 254nm <1 ppb; 365nm <1 ppb  
Suitability for LC-MS passes test  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Suitability for PFAS analysis passes test  
Application: Ultra low background solvent for LC-MS analysis of poly- and perfluoroalkyl substances

**iso-Octane (see 2,2,4-Trimethylpentane)**

**iso-Propanol (see Propan-2-ol)**

**Propanone (see Acetone)**

**iso-Propyl Alcohol (see Propan-2-ol)**







**RIKI GLOBAL**  
performance through innovation

## ROMIL-UpS™ Ultra Purity Solvents Specifications

for critical analytical applications

### n-Pentane 95% UpS

ultra gc

H574

2½LT H574L  
Dgr H:225-304-336-411-EUH066  
P:273-301+310-331-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>3</sub>CH<sub>3</sub> MW 72.15 BP 36.0°C d 0.63 CAS [109-66-0] Water <0.005% Residue <0.0001% Assay (n-isomer) >95% Assay (all isomers) >99.5% Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test Application:GCcritical lowresidue applications

### n-Pentane 99% UpS

ultra gc

H573

2½LT H573L  
Dgr H:225-304-336-411-EUH066  
P:273-301+310-331-403+235



CH<sub>3</sub>(CH<sub>2</sub>)<sub>3</sub>CH<sub>3</sub> MW 72.15 BP 36.0°C d 0.63 CAS [109-66-0] Assay >99% Water <0.01% Residue <0.0001% Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test Application:GCcritical lowresidue applications

### Propan-2-ol UpS

ultra lc

H626

1LT H626M  
2½LT H626L  
Dgr H:225-319-336  
P:210-233-305+351+338



(**iso-Propanol, iso-Propyl Alcohol**)  
(CH<sub>3</sub>)<sub>2</sub>CHOH MW 60.10BP 82.2°C d 0.78 CAS [67-63-0]

Assay >99.9% Water <0.02% Residue <0.0001% UV: 205nm >10%; 210nm >50%; 225nm >80%; 240nm >95%; 255-400nm >99% Acidity <0.0002 meq/g Alkalinity <0.0002 meq/g Gradient Use Test: 254nm <0.005 AU Fluorescence (as quinine): 254nm <1 ppb; 365nm <1 ppb Suitability for LC-MS passes test Trace ionic impurities: Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each Al, Ca <25 ppb each Na <50 ppb Application: HPLC critical gradient applications, LC-MS, UHPLC

### Tetrahydrofuran UpS

ultra lc

H720

1LT H720M  
2½LT H720L  
Dgr H:225-319-335-351-EUH019  
P:210-240-305+351+338-308+313-403+233



CH<sub>2</sub>(CH<sub>2</sub>)<sub>2</sub>CH<sub>2</sub>O MW 72.11 BP 66.0°C d 0.89 CAS [109-99-9] Assay >99.9% Water <0.005% Residue <0.0001% UV: 215nm >10%; 235nm >50%; 255nm >80%; 275nm >95%; 295-400nm >99% Unstabilised Peroxides (at time of manufacture) <0.0001% (<1 ppm) Acidity <0.0005 meq/g Alkalinity <0.0005 meq/g Gradient Use Test: 290nm <0.0005 AU Fluorescence (as quinine): 254nm <1 ppb; 365nm <1 ppb Suitability for LC-MS passes test Trace ionic impurities: Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each Al, Ca <25 ppb each Na <50 ppb Application: HPLC critical gradient applications, LC-MS, UHPLC

### Toluene UpS

ultra gc

H772

2½LT H772L  
Dgr H:225-304-315-336-361d-373  
P:210-240-301+310-331-302+352-403+235



C<sub>6</sub>H<sub>5</sub>CH<sub>3</sub> MW 92.14 BP 110.6°C d 0.87 CAS [108-88-3] Assay >99.9% Water <0.01% Residue <0.0001% Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test Application:GC critical lowresidueapplications

### 2,2,4-Trimethylpentane UpS

ultra gc

H903

2½LT H903L  
Dgr H:225-304-315-336-410  
P:210-233-240-273-301+310-331-302+352-304+340-403+235



(**iso-Octane**)  
(CH<sub>3</sub>)<sub>3</sub>CCH<sub>2</sub>CH(CH<sub>3</sub>)<sub>2</sub> MW 114.23 BP 99.2°C d 0.69 CAS [540-84-1] Assay >99.75% Water <0.01% Residue <0.0001% Suitability for GC-FID passes test Suitability for GC-ECD passes test Suitability for GC-MS passes test Application: GC critical low residue applications





**RIKI GLOBAL**  
performance through innovation

## ROMIL-UpS™ Ultra Purity Solvents Specifications

for critical analytical applications

### Water UpS

#### ultra lc

1LT H949M  
2½LT H949L

H<sub>2</sub>O MW 18.02 FP 0.0°C BP 100.0°C d 1.00 CAS [7732-18-5]  
Residue <0.00005%  
Resistivity (at time of manufacture) >18 MOhm @ 25°C  
pH (at time of manufacture) 5.5-8.0 @ 25°C  
TOC (at time of manufacture) <10 ppb  
Gradient Use Test: 205nm <0.002 AU; 254nm <0.0005 AU  
Baseline drift <0.02 AU @ 205nm  
Suitability for LC-MS passes test  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Filtered to 0.2 micron  
Application: HPLC critical gradient applications, LC-MS, UHPLC

H949

### Water UpS

#### ultra pfas

2½LT H952L

H<sub>2</sub>O MW 18.02 FP 0.0°C BP 100.0°C d 1.00 CAS [7732-18-5]  
Residue <0.00005%  
Resistivity (at time of manufacture) >18 MOhm @ 25°C  
pH (at time of manufacture) 5.5-8.0 @ 25°C  
TOC (at time of manufacture) <10 ppb  
Gradient Use Test: 205nm <0.002 AU; 254nm <0.0005 AU  
Baseline drift <0.02 AU @ 205nm  
Suitability for LC-MS passes test  
Trace ionic impurities:  
Ag, Cu, Fe, K, Mg, Mn, Ni, Pb, Zn <10 ppb each  
Al, Ca <25 ppb each  
Na <50 ppb  
Suitability for PFAS analysis passes test  
Filtered to 0.2 micron  
Application: Ultra low background solvent for LC-MS analysis of poly- and per-  
uoroalkyl substances

H952

